

Call for Papers

3 Steps to Contribute a Presentation

Join JSAP

Regular Membership

Admission Fee: 10,000 JPY Annual Due*: 10,000 JPY

*Annual due will be waived for

the first year.

Graduate Student/ Student Membership

Admission Fee: 3,000JPY Annual Due*: 3,000 JPY

*Annual due will be waived for the first year.

Submit

Submission Deadline:

June 25 (Tue.), 2019 (17:00, JST)

No late submission is accepted after the deadline.

Online submission will open in May 24 (Fri.).

Register

Registration Deadline:

August 26 (Mon.), 2019

Advanced

JSAP Official Member /

Partner Society Member: 12,000 JPY JSAP Senior Member: 4,000 JPY

Student: 3,000 JPY

Non-member: 23,000 JPY

Onsite

JSAP Official Member /

Partner Society Member: 18,000 JPY

JSAP Senior Member: 7,000 JPY

Student: 5,000 JPY Non-member: 30,000 JPY

Online pre-registration open on

May 24 (Fri.).

Submission Deadline

June 25 (Tue.), 2019 (5:00pm, JST)

*No late submission is accepted.

Call for Papers

Papers are solicited for the following sessions (table 1-3) and symposia.

The date and section of your presentation will be determined by our program committee and informed you in early July. Your papers may be forwarded from a regular session to a symposium and vice versa.

Table 1. Focused Session

Focused Session		(Keywords)
"AI Electronics"	31.1	newromorphic, brain computer, synapse, STDP, neural network, neural circuit,
		reservoir computing

Table 2. Regular Sessions			
Category		Section	
1 Interdisciplinary Physics and Related	1.1	Interdisciplinary and General Physics	
Areas of Science and Technology	1.2	Education	
	1.3	Novel technologies and interdisciplinary engineering	
	1.4	Energy conversion, storage, resources and environment	
	1.5	Instrumentation, measurement and Metrology	
	1.6	Ultrasonics	
2 Ionizing Radiation	2.1	Radiation physics and Detector fundamentals	
-	2.2	Detection systems	
	2.3	Application, radiation generators, new technology	
	2.4	Accelerator Mass Spectrometry, Accelerator Beam Analysis	
3 Optics and Photonics	3.1	Basic optics and frontier of optics	
	3.2	Equipment optics and materials	
	3.3	Information photonics and image engineering	
	3.4	Biomedical optics	
l	3.5	Laser system and materials	
	3.6	Ultrashort-pulse and high-intensity lasers	
l	3.7	Laser processing	
	3.8	Optical measurement, instrumentation, and sensor	
	3.9	Terahertz technologies	
	3.10	Optical quantum physics and technologies	
	3.11	Photonic structures and phenomena	
	3.12	Nanoscale optical science and near-field optics	
	3.13	Semiconductor optical devices	
	3.14	Optical control devices and optical fibers	
	3.15	Silicon photonics	
4 JSAP-OSA Joint Symposia	4.1	Plasmonics and Nanophotonics	
, ,	4.2	Photonics Devices, Photonic Integrated Circuit and Silicon Photonics	
	4.3	Ultrafast Optics and Laser Processing	
	4.4	Information Photonics	
	4.5	Terahertz Photonics	
	4.6	Quantum Optics and Nonlinear Optics	
6 Thin Films and Surfaces	6.1	Ferroelectric thin films	
	6.2	Carbon-based thin films	
	6.3	Oxide electronics	
	6.4	Thin films and New materials	
	6.5	Surface Physics, Vacuum	
	6.6	Probe Microscopy	
7 Beam Technology and Nanofabrication		X-ray technologies	
		Applications and technologies of electron beams	
	7.3	Micro/Nano patterning and fabrication	
	7.4	Buried interface sciences with quantum beam	
		lon beams	
		Atomic/molecular beams and beam-related new technologies	

Table 2. Regular Sessions (continued)				
Category		Section		
8 Plasma Electronics	8.1	Plasma production and diagnostics		
*All-English session is scheduled in the section 8.6	8.2	Plasma deposition of thin film, plasma etching and surface treatment		
	8.3	Plasma nanotechnology		
	8.4	Plasma life sciences		
	8.5	Plasma phenomena, emerging area of plasmas and their new applications		
	8.6	Plasma Electronics English Session		
9 Applied Materials Science	9.1	Dielectrics, ferroelectrics		
	9.2	Nanoparticles, Nanowires and Nanosheets		
	9.3	Nanoelectronics		
	9.4	Thermoelectric conversion		
	9.5	New functional materials and new phenomena		
10 Spintronics and Magnetics	10.1	Emerging materials in spintronics and magnetics (including fabrication and charactrization methodologies)		
*English presentations are welcomed in this	10.2	Fundamental and exploratory device technologies for spin		
category. Outstanding presentations by student speakers will be awarded by	10.3	Spin devices, magnetic memories and storages		
Professional Group of Spintronics.	10.4	Semiconductor spintronics, superconductor, multiferroics		
Trolessional Group of Spinitonies.	10.4	Application of magnetic field		
11 Superconductivity	11.1	Fundamental properties		
11 Superconductivity	11.2	Thin and thick superconducting films, coated conductors and film crystal growth		
	11.3	Critical Current, Superconducting Power Applications		
	11.4	Analog applications and their related technologies		
	11.5	Junction and circuit fabrication process, digital applications		
12 Organic Molecules and	12.1	Fabrications and Structure Controls		
Bioelectronics	12.2	Characterization and Materials Physics		
Bioelecti offics	12.3	Functional Materials and Novel Devices		
	12.4	Organic light-emitting devices and organic transistors		
	12.5	Organic solar cells		
	12.6	Nanobiotechnology		
	12.7	Biomedical Engineering and Biochips		
13 Semiconductors *All-English session is scheduled in the	13.1	Fundamental properties, surface and interface, and simulations of Si related materials		
section 13.6.	13.2	Exploratory Materials, Physical Properties, Devices		
	13.3	Insulator technology		
	13.4	Si processing /Si based thin film / MEMS / Equipment technology		
	13.5	Semiconductor devices/ Interconnect/ Integration technologies		
	13.6	Nanostructures, quantum phenomena, and nano quantum devices		
	13.7	Compound and power electron devices and process technology		
	13.8	Optical properties and light-emitting devices		
	13.9	Compound solar cells		
15 Crystal Engineering	15.1	Bulk crystal growth		
	15.2	II-VI and related compounds		
	15.3	III-V-group epitaxial crystals, Fundamentals of epitaxy		
	15.4 15.5	III-V-group nitride crystals Group IV crystals and alloys		
	15.5	Group IV Compound Semiconductors (SiC)		
	15.6	Crystal characterization, impurities and crystal defects		
16 Amorphous and	16.1	Fundamental properties, evaluation, process and devices in disordered materials		
Microcrystalline Materials	16.2	Energy Harvesting		
	16.3	Bulk, thin-film and other silicon-based solar cells		
17 Nanocarbon Technology	17.1	Carbon nanotubes & other nanocarbon materials		
TA Maniocarbon recimology	17.2	Graphene		
	17.3	Layered materials		
	17.3			

Table 3. Joint Sessions

Joint Session K "Wide bandgap oxide semiconductor materials and devices"	21.1	(Keywords) thin film growth, characterization of physical properties, transparent conductive oxide film, electronic devices, optical devices, novel functional materials & development of novel technologies
Joint Session M "Phonon Engineering"	22.1	(Keywords) material development and material properties, measurement methods, theory and simulation, thermal conduction and phonon transport, nanoscale and low dimensional system, band engineering, coherent control, phonon polariton, magnon, thermal management and design technology, device application, thermoelectrics, thermal storage, thermal insulation, micro/nanomechanics, heat dissipation, thermal conversion, nano-structure/device fabrication technology
Joint Session N "Informatics"	23.1	(Keywords) materials informatics, measurement informatics, data science, data mining, machine learning, sparse modeling, deep learning, Bayes optimization, data assimilation

Table 4. Symposium

See https://meeting.jsap.or.jp/english/symposium

Submission Guidelines (for contributed papers)

1 Qualification

Speakers of contributed presentation (oral and poster presentations) should be JSAP Regular Members, Student Members and JSAP's Partner Societies* Members.

*JSAP's partner societies: American Physical Society (APS), CSOE(Chinese Society for Optical Engineering), European Optical Society (EOS), European Physical Society (EPS), Institute of Physics (IOP), Korean Physical Society (KPS), Optical Society of America (OSA), Optical Society of Japan (OSJ), Optical Society of Korea (OSK), Physics Education Society of Japan (PESJ), Physical Society of Republic of China (PSROC), Société Française de Physique (SFP), International Society for Optical Engineering (SPIE) and Taiwan Photonics Society (TPS).

2. Handling of abstract (PDF)

- 1) Our program committee draws up a program according to speakers' requests. However, the program committee may forward your abstract to another category for the benefit of the overall program.
- 2) JSAP holds the copyright on the submitted abstracts and all the submitted abstracts will be included in the abstracts DVD-ROM and uploaded on the online conference program.
- 3) The abstracts submitted to the JSAP-OSA Joint Symposia (held only in JSAP Autumn Meeting) will be published in OSA's Optics InfoBase. JSAP grants to OSA a perpetual, non-exclusive, royalty-free license to use them in any type of media including print or electronic.
- 4) The maximum number of submission per person is 3.

3. JSAP Young Scientist Presentation Award

JSAP Young Scientist Presentation Award will be presented to young JSAP members (under 33 years of age as of April 1, 2020) who have presented outstanding papers.

To apply for the award, please select "apply" upon online submission. Applicants for the award will be indicated as such in the program.

4. Poster Awards

Poster Awards will be given to the outstanding posters. The nominees for Poster Awards will be selected by our program committee. No entry is required.

The authors of the nominated posters will be informed beforehand. The next screening will be done during the first 30 minutes of the session. The presenting authors of the nominated posters should be present in front of their posters during that time. Selection committee will vote and decide the final winner.